

## JENS GOBRECHT

### List of Publications and Patents

#### Articles in Journals or Proceedings (peer review)

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**Books:**

J. Gobrecht: Chapter 9: "Der elektrische Strom in festen Körpern" and chapter 10: "Elektrischer Strom in Flüssigkeiten" in "*Bergmann-Schaefer, Lehrbuch der Experimentalphysik*", H. Gobrecht (Hrsg.), Walter de Gruyter, Berlin, New York 1987.

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J. Gobrecht: Chapter 1: “Rückblick auf die Entstehungsgeschichte der Nanotechnologie” and chapter 5: “Die Evolution der neuen Produktionsverfahren”; in “Highlights aus der Nanowelt – eine Schlüsseltechnologie verändert unsere Gesellschaft”, ed. By Marianne Oesterreicher; Herder Verlag, Freiburg i.Br., 2006; ISBN-10: 3-451-05672-0

## Patents

<b>Nr.</b>	<b>Inventors</b>	<b>Title</b>	<b>Status</b>
1	J.Gobrecht C. Schüler	Elektrischer Kontakt für Silizium-Halbleiter	Erteilt in CH, DE, FR, GE, Li, SE
2	J.Gobrecht	Verfahren zum direkten Verbinden eines Körpers mit einem keramischen Substrat	Nach Anmeldung in DE nicht weiterverfolgt
3	J.Gobrecht	Keramik-Metall-Element	Erteilt in USA u. Europa
4	J. Gobrecht P. Roggwiller J.Voboril	Abschaltbares Leistungshalbleiter Bauelement und Verfahren zu seiner Herstellung	Erteilt in USA u. Europa
5	J.Gobrecht	Verfahren zum Löten von Halbleiterbauelementen	Nach Anmeldung in CH nicht weiterverfolgt
6	G. Nippert B. Hahn J. Gobrecht	Leistungshalbleitermodul	Erteilt in USA
7	A. Neidig K. Bunk J. Gobrecht	Leistungshalbleitermodul	Erteilt in USA u. Europa
8	A. Neidig J.Gobrecht	Kontaktelektrode für Leistungshalbleiter-Bauelemente	Angemeldet
9	A. Neidig K. Bunk Thiele G. Wahl J. Gobrecht	Verfahren zum direkten Verbinden von von Metall mit Keramik	Erteilt in USA
10	J. Gobrecht	Elektronisches Schaltungsmodul	Erteilt in CH
11	J. Gobrecht M. Rossinelli	Trockenätzverfahren	Erteilt in USA u. Europa
12	J. Gobrecht A. Neidig	Metall-Keramik-Verbundelement und Verfahren zu dessen Herstellung	Angemeldet in USA, Europa
13	J.Gobrecht	Kollektor für eine elektrische Maschine	Erteilt in USA u.

	C. Schüler	und Verfahren zu dessen Herstellung	UdSSR
14	J. Gobrecht P.Roggwiller J. Voboril B. Broich	Abschalbares Leistungshalbleiter-Bauelement und Verfahren zu dessen Herstellung	Nach Anmeldung in CH nicht weiterverfolgt
15	B.Broich J. Gobrecht P. Roggwiller J. Voboril	Abschalbares Leistungshalbleiter-Bauelement	Angemeldet
16	J.Gobrecht R.Bayerer	Leistungshalbleitermodul	Erteilt in USA
17	J. Gobrecht	Verfahren zum Verbinden von gesintertem Silizium-Karbid mit Kupfer	Angemeldet
18	B. Broich J. Gobrecht P.Roggwiller	Leistungshalbleiter-Modul	Erteilt in USA
19	J.Gobrecht J.Voboril	Verfahren zur Herstellung einer Abdeckschicht für die Halbleitertechnik sowie Verwendung der Abdeckschicht	Erteilt in USA
20	J. Gobrecht H. Grüning J. Voboril	Halbleiterbauelement sowie Verfahren zu dessen Herstellung	Angemeldet
21	J. Gobrecht J. Pethica	Verfahren zur Erzeugung feiner Strukturen in einem Substrat und Vorrichtung zur Durchführung des Verfahrens.	Nach Anmeldung in CH nicht weiterverfolgt
22	C.Abbas J.Gobrecht H. Grüning J.Voboril	Halbleiter-Bauelement	Erteilt in USA
23	A. Neidig J. Gobrecht K. Exel	Vorrichtung zum Benetzen von Flächen mit Lot	Angemeldet
24	F.Bauer J. Gobrecht T. Stockmeier	Bipolares, über ein Gate abschaltbares Leistungshalbleiter-Bauelement	Angemeldet



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| 25 | F.Bauer<br>J.Gobrecht  | Thyristor mit MOS-gesteuertem Hilfs-IGBT   | Angemeldet                             |
| 26 | F. Bauer<br>J. Gobrecht  | Abschaltbares, MOS gesteuertes Leistungshalbleiter-Bauelement sowie Verfahren zu dessen Herstellung  | Angemeldet                             |
| 27 | M. Schaldach<br>J. Gobrecht<br>C. Kranz                                | Vorrichtung zur automatischen Durchführung von diagnostischen und/oder therapeutischen aktionen in Körperhöhlungen   | Erteilt<br>EP 1 174 076 A2             |
| 28 | K.-P. Schmitz<br>J. Gobrecht<br>D. Behrend<br>M. Schaldach<br>A. Rzany | Selbststeuernder Katheter zur Anwendung im oder am Herzen  | Erteilt<br>DE, FR, GB, IT, NL, CH, USA |
| 29 | M. Schaldach<br>K.-P. Schmitz<br>J. Gobrecht<br>A.Rzany<br>D. Behrend  | Verfahren zum Anbringen eines Marker- Elementes an einem Implantat sowie mit einem Markerelement versehenes Implantat  | Erteilt<br>DE10064596.8                |
| 30 | H. Solak<br>Ch. Kambach<br>J. Gobrecht                                 | Method for generating an artificially patterned substrate for stimulating the crystallization of an biomolecule thereon and method for stimulation of biomolecules | Angemeldet<br>EPA 02 003 534.1         |